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# **INFORMATION DISCLOSURE STATEMENT BY APPLICANT**

(use as many sheets as necessary)

Complete if Known

Application Number	09/876,955
Confirmation Number	4359
Filing Date	June 7, 2001
First Named Inventor	Shirley HEMAR
Art Unit	2625
Examiner Name	John B. STREGE
Attorney Docket Number	005329 USA Y1/MASK/RT/OR

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## **U.S. PATENT DOCUMENTS**

Examiner Initials*	Cite No. <sup>1</sup>	Document Number		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document
		Number	Kind Code <sup>2</sup> (if known)		
JS	—	US 5,838,433		11-17-1998	Hagiwara
	—	US 5,563,702		10-08-1996	Emery et al.
	—	US 3,725,574		04-03-1973	Gast
	—	US 4,926,489		05-15-1990	Danielson et al.
	—	US 5,210,635		05-11-1993	Nagata et al.
	—	US 4,595,289		06-17-1986	Feldman et al.
	—	US 5,892,579		04-06-1999	Elyasaf et al.
	—	US 6,124,924		09-26-2000	Feldman et al.
	—	US 6,466,315		10-15-2002	Karpol et al.
		US			
		US			

## **FOREIGN PATENT DOCUMENTS**

Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document			Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Translation <sup>6</sup>
		Country Code <sup>3</sup>	Number <sup>4</sup>	Kind Code <sup>5</sup> (if known)			

## **NON PATENT LITERATURE DOCUMENTS**

Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city, and/or country where published.	Translation <sup>6</sup>
JS	—	FERGUSON, RICHARD A., ET AL., "Application of an Aerial Image Measurement System to Mask Fabrication and Analysis," SPIE Vol. 2087 13 <sup>th</sup> Annual Symposium on Photomask Technology and Management, Sept. 22-23, 1993, Santa Clara, California, pp. 131-144.	—

Examiner Signature

*John Strege*

Date Considered

12/7/05